



DT07 Rec'd PCT/PTO 26 NOV 2004

PCT

PATENT #3

Practitioner's Docket No. FMW-BR-PCT-US

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Marco Wedowski et al.

Group No.:

Application No.: 10/506,555

Examiner:

Filed:

Date: November 22, 2004

For: **DEVICE, EUV-LITHOGRAPHIC DEVICE AND METHOD FOR PREVENTING AND CLEANING CONTAMINATION ON OPTICAL ELEMENTS**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

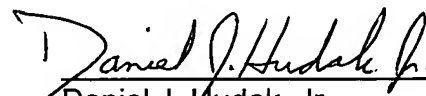
CERTIFICATE OF MAILING

Sir:

The undersigned hereby certifies that the attached **INFORMATION DISCLOSURE STATEMENT, FORM PTO-1449, AND FIVE (5) REFERENCES** were mailed to the Commissioner for Patents, Alexandria, VA 22313-1450, with sufficient first-class postage, no special handling, on November 22, 2004, before 5:00 PM, thereby ensuring that such document(s) will be in the hands of the U.S. Postal Service by the close of business this day.

Respectfully submitted,

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**PATENT**

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**INFORMATION DISCLOSURE STATEMENT**

Sir:

The invention relates to a method for preventing contamination on the surfaces of optical elements comprising a multi-layer system, during the exposure thereof to radiation at signal wave lengths in an evacuated closed system comprising a residual gas atmosphere, whereby the photocurrent generated by means of photo emission from the radiated surface of the multi-layer system is measured. The photocurrent is used to regulate the gas composition of the residual gas. The gas composition is altered according to at least one lower and one upper threshold value of the photocurrent. The invention also relates to a device for regulating the contamination on the surface of at least one optical element during exposure and an EUV-lithographic device and a method for cleaning the surfaces of the optical elements contaminated by carbon.

As authorized and encouraged under 37 C.F.R. §1.97-1.99, applicant hereby cites as a means of complying with the duty of disclosure set forth in 37 C.F.R. §1.56, the following patents and/or documents, which the Examiner should consider with respect to the above-identified U.S. patent application:

U.S. DOCUMENTS		
PATENT/DOCUMENT NO.	DATE	INVENTOR(S)
6,545,272	April 8, 2003	Kondo
6,004,180	Dec. 21, 1999	Knall et al.
4,998,019	March 5, 1991	Stokowski et al.
FOREIGN DOCUMENTS		
DOCUMENT NO.	DATE	COUNTRY
DE 4106841 A1 (w/translation U.S. 4,998,019)	Sept. 10, 1992	DE
JP 62051224 A (w/English Abstract)	March 5, 1987	JP
EP 0 987 601 A2	March 22, 2000	EP
JP 2000-346817 (w/translation U.S. 6,545,272)	Dec. 15, 2000	JP
PUBLICATIONS		
"Soft X-Ray and EUV Imaging Systems II", Daniel A. Tichenor, James A. Folta, <i>Proceedings of The International Society of Optical Engineering</i> , July 31-August 1, 2001, San Diego, USA, Volume 4506, pages 93-104		

As this application was filed after June 30, 2003, only copies of the foreign documents and publications are included for the express purpose of providing the Patent and Trademark Office with an ample opportunity to evaluate the same and to arrive at an independent assessment of their materiality, if any, with regard to the examination of the application.

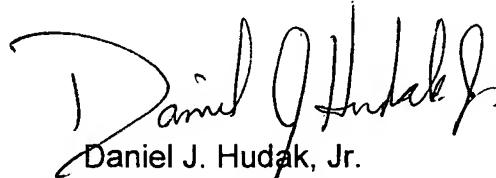
In reviewing the enclosed copies of the above publications, the Examiner is requested to ignore any underscoring or highlighting which may appear because such markings may or may not have any relationship to the subject matter of the above-identified application. The copies being submitted with this Information Disclosure Statement are the best copies available at this time.

An examination of the present application considering the above documents is requested.

The Commissioner is hereby authorized to charge any fees that might be required or credit any overpayment of fees with regard to this document to Deposit Account No. 08-3150.

Respectfully submitted,

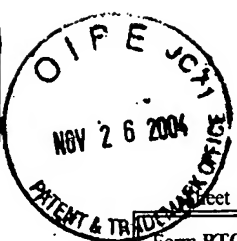
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Attorney Docket No. FMW-BR-PCT-U



Sheet 1 of 1

Form PTO-1449 U.S. Department of Commerce Patent and Trademark Office LIST OF PRIOR ART CITED BY APPLICANT (Use several sheets if necessary)				Atty. Docket No.: FMW-BR-PCT-US		Serial No.: 10/506,555	
				Applicant: Marco Wedowski et al.			
				Filing Date:		Group:	
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing date if appropriate
	AA	6,545,272	April 8, 2003	Kondo			
	AB	6,004,180	Dec. 21, 1999	Knall et al.			
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	AD						
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	AK						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	<u>Translation</u> Yes No
	AL	41 06 841 A1	Sept. 10, 1992	Germany			X
	AM	62051224	Mar. 5, 1987	Japan			X
	AN	0 987 601 A2	Mar. 22, 2000	EP			
	AO	2000 346817	Dec. 15, 2000	Japan			X
	AP						
OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
	AR		"Soft X-Ray and EUV Imaging Systems II", Daniel A. Tichenor, James A. Folta, <i>Proceedings of The International Society of Optical Engineering</i> , July 31-August 1, 2001, San Diego, USA, Volume 4506, pages 93-104				
	AS						
EXAMINER				DATE CONSIDERED			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							